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DERWENT-WEEK: 200482

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TITLE: Semiconductor fabricating apparatus for supplying  
process gas to inside of tube

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PATENT-FAMILY:

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KR 444753 B	August 21, 2004	N/A	000
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APPLICATION-DATA:

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ABSTRACTED-PUB-NO: KR2003039670A

BASIC-ABSTRACT:

NOVELTY - A semiconductor fabricating apparatus for supplying process gas to the inside of a tube is provided to rapidly exhaust reaction gas and minimize generation of particles by making the flow path of the reaction gas short, and to improve uniformity by uniformly supplying the reaction gas regardless of the position in a process chamber.

DETAILED DESCRIPTION - A plurality of wafers are loaded into a boat (140).

A reaction furnace has a closed inner space into which the boat is loaded. A

shower head(120) uniformly sprays the reaction gas on the inner space of the reaction furnace, installed in the sidewall of the reaction furnace.

CHOSEN-DRAWING: Dwg.1/10

TITLE-TERMS: SEMICONDUCTOR FABRICATE APPARATUS SUPPLY PROCESS GAS TUBE

DERWENT-CLASS: U11

EPI-CODES: U11-C01B;

100

